

Title (en)  
REMOVAL OF MASKING MATERIAL

Title (de)  
ENTFERNUNG EINES MASKIERUNGSMATERIALS

Title (fr)  
ÉLIMINATION D'UNE MATIÈRE DE MASQUAGE

Publication  
**EP 2510538 A4 20140326 (EN)**

Application  
**EP 10836729 A 20101210**

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• US 2010059800 W 20101210

Abstract (en)  
[origin: WO2011072188A2] Methods for removing a masking material, for example, a photoresist, and electronic devices formed by removing a masking material are presented. For example, a method for removing a masking material includes contacting the masking material with a solution comprising cerium and at least one additional oxidant. The cerium may be comprised in a salt. The salt may be cerium ammonium nitrate. The at least one additional oxidant may be a manganese, ruthenium, and/or osmium-containing compound.

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CPC (source: EP KR)  
**G03F 7/423** (2013.01 - EP); **H01L 21/3063** (2013.01 - KR); **H01L 21/31133** (2013.01 - EP)

Citation (search report)  
• [I] US 2008283090 A1 20081120 - DEKRAKER DAVID [US], et al  
• [X] WO 2006113621 A2 20061026 - ADVANCED TECH MATERIALS [US], et al  
• See references of WO 2011072188A2

Designated contracting state (EPC)  
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DOCDB simple family (publication)  
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